PAT-NO:

JP401230478A

DOCUMENT-IDENTIFIER: JP 01230478 A

TITLE:

HOMOGENEOUS SINTERED SILICON NITRIDE

AND PRODUCTION

THEREOF

PUBN-DATE:

September 13, 1989

INVENTOR - INFORMATION: NAME HAYAKAWA, KAZUMORI ITO, SHIGENORI

ASSIGNEE-INFORMATION:

NAME

NGK INSULATORS LTD

COUNTRY

A/N

APPL-NO:

JP63044001

APPL-DATE:

February 26, 1988

INT-CL (IPC): C04B035/58

## ABSTRACT:

PURPOSE: To obtain a uniform and high-strength sintered silicon nitride, by mixing, pulverizing, granulating and forming a silicon nitride raw material and a sintering assistant, calcining the formed article and cooling at a specific cooling rate.

CONSTITUTION: A silicon nitride raw material and a sintering assistant are mixed, pulverized, granulated and formed, and the obtained formed article is calcined to obtain a sintered silicon nitride. In the above process, the

in the atmosphere under 1-2 atm pressure and held at 1,400-1,600°C preferably for 0.5-2 hr until it is made substantially free from open pores. the 2nd stage, the pressure of the atmosphere is increased to ≥ 30 atm and the green compact is held at 1,400-1,600° C preferably for 2-5 hr until the residual α -rate of the resultant sintered compact attains to 5-35%. sintered compact contains 4-10 wt.% (expressed in terms of Yb<SB>2</SB>O<SB>3</SB>) Yb, 2-5 wt.% (expressed in terms of MgO) Mg and 0.5-4 wt.% (expressed in terms of Al<SB>2</SB>O<SB>3</SB>) Al and the weight ratio of A1<SB>2</SB>O<SB>3</SB> to MgO is ≤1.

COPYRIGHT: (C)1999, JPO